Chen Xu, a William and Mary Ph.D. student in Applied Science under the direction of Dr. Michael Kelley, presented the results of his research on surface roughness and implications on cavity performance at the TELSLA Technology Collaboration Meeting hosted by Jefferson Lab on November 6th. Chen is performing research at Jefferson Lab on superconducting radiofrequency cavity design and processing for future accelerators.

Anil Poda is pictured here analyzing his nano filled polypropylene dielectric material using one of our Hirox microscopes. Anil is performing research to support his master's degree program in Electronics at Norfolk State University under the direction of Dr. Prathap Basappation.